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Optical equipment for artificial sunlight exposure apparatus - consists of mosaic filter chips differing in filtering characteristic NoAbstract

Dwg 1-3/6

Patent Assignee: KAZUHIRO TAKESHI (KAZU-N)

Number of Countries: 001 Number of Patents: 001

Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date	Week
JP 3252604	A	19911111	JP 9051373	A	19900302	199151 B

Priority Applications (No Type Date): JP 9051373 A 19900302

Abstract (Basic): JP 3252604 A

A first layer comprising GeO₂, a second layer comprising a complex of TiO₂ and HfO₂ or comprising TiO₂, and a third layer comprising SiO₂ are laminated successively on a synthetic resin optical component.

The synthetic resin optical component pref. comprises a polycarbonate resin. The first, second, and third layers are formed to have a thickness of 0.25 lambda to the design wavelength (lambda) of applied light.

USE/ADVANTAGE - The anti-reflection film applies to synthetic resin optical components and finds its application in office automation machines, optical communications, optical information processing, or cameras. The film substances have high chemical and thermal stability. The anti-reflection film has good adhesion to the synthetic resin base material and maintains high reflectance, for a wide wavelength region, and features superior durability. (5pp Dwg.No.0/5)